

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims

1- 2. (Cancelled)

3. (Currently Amended) A power supply antenna, comprising:

at least two coils disposed concentrically and having adjustable radii, the at least two coils comprising

a plurality of conductors bent into a form of an arc, and

power supply portions formed at opposite ends of the respective coils so as to be connected to a high frequency power source, said power supply portions located in different phases on a common plane; and

another coil disposed on a plane parallel to the common plane ~~and configured to vary mutual inductances so that a distribution of energy absorbed to a plasma is adjusted.~~

4. (Previously Presented) The power supply antenna of Claim 3, wherein:
spacing between adjacent power supply portions in the respective coils is equal.

5-10. (Cancelled).

11. (Currently Amended) A semiconductor manufacturing apparatus comprising:

a vessel having an electromagnetic wave transparent window;

a power supply antenna provided outside the vessel and opposed to the electromagnetic wave transparent window; and

a power source for applying a high frequency voltage to the power supply antenna, and being adapted to apply the high frequency voltage from the power source to the power supply antenna to generate an electromagnetic wave, and pass the electromagnetic wave through the electromagnetic wave transparent window into the vessel to generate a plasma, thereby treating a surface of a substrate in the vessel, wherein

the power supply antenna comprises

at least two coils disposed concentrically and having adjustable radii, the at least two coils comprising

a plurality of conductors each into a form of an arc, and

power supply portions formed at opposite ends of the respective coils so as to be connected to a high frequency power source, said power supply portions located in different phases on a common plane; and

another coil disposed on a plane parallel to the common plane ~~and configured to vary mutual inductances so that a distribution of energy absorbed to a plasma is adjusted.~~

12-17. (Cancelled).